

AR-P 3510T – run sheet

Allresist

nanyte.com/photoresists/ar-p-3510t · last updated 2026-07-26

Thickness: 2 μm

Softbake: 100 °C · 60 s · hotplate

Develop: Developer AR 300-26 (1:2) or AR 300-35 (undiluted) or AR 300-44 · Dilution AR 300-26 at 1:2; AR 300-35 used undiluted; AR 300-44 listed as the third (ready-to-use) option – three alternative developer/dilution combinations named for the combined 'AR-P 3510 T, 3540 T' row of the 'Development recommendations' table (p.1). This differs from the base AR-P 3510/3540 row, which instead lists AR 300-26 at 1:5, AR 300-35 at 1:1, and 'AR 300-40 (300-47), 1:1'. · Rinse DI-H2O, 30 s · Method puddle

Hardbake: 115 °C · 60 s